

METHOD AND SYSTEM FOR
PROCESSING SEMICONDUCTOR WAFERS

ABSTRACT OF THE DISCLOSURE

5 A method for processing semiconductor wafers includes processing a semiconductor wafer in a processing chamber having upper and lower chambers, decoupling the upper chamber from the lower chamber, cleaning the upper chamber, determining, while decoupled, that a leak rate and a particle count for the upper chamber meets predetermined criteria, and coupling the upper chamber to the lower
10 chamber.